Supporting Information

Enhanced photocatalytic activity of TiO_2 thin film deposited by reactive RF-sputtering under oxygen-rich conditions

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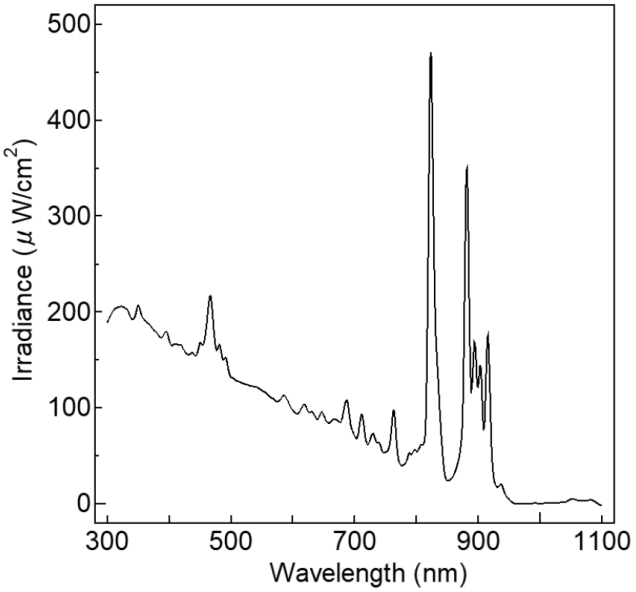


Figure S1 Spectral irradiance of the Xenon lamp

Table S1 The comparison of sputtering condition in several pieces of literature

Substrate temperature	R_{O2} (%)	Reference
Unheated	0-70	This work
Unheated (approximately 130 °C)	34.5-59.8	[17]
Unheated - 120℃	40-80	[18]
400 ℃	0-70	[19]

Table S2 The crystallite size of TiO_2 thin films estimated via Scherrer's equation based on anatase (101) plane

R_{O2} (%)	nm
5	49.7
10	42.1
20	39.6
30	37.2
40	35.6
50	46.2
60	43.2
70	38.9